

What is claimed is:

1. An apparatus for coating a substrate, the apparatus comprising:

5 a coating source for processing the substrate;

a sensor that generates a sensor signal at an output that
is related to the actual status of the coating process; and

10 means for generating a control signal related to the sensor
signal for modifying at least one operating parameter of the
coating source during the processing of the substrate, wherein
the sensor signal does not reflect the at least one operating
parameter.

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2. A method for processing a substrate, the method comprising:

processing the substrate in a treatment area of a treatment
source substantially according to a predetermined scheme
20 comprising a set of parameters;

selecting a subset of said set with at least one parameter as
control parameter(s) and at least one further parameter not
comprised in said subset as operating parameter(s);

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determining a deviation of the subset from the predetermined
scheme;

30 generating a control signal in response to the determined
deviation; and

modifying the at least one operating parameter(s) in response to
the control signal to compensate for an effect of the deviation
from the predetermined scheme.

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